

# Oxidation system for VCSELs Production (HiVOX6001)

## Features

- With in-situ monitoring system
- Precise Oxidation Ability  
(High uniformity, High reproducibility)
- Compact system
- Maintenance improvement
- Automation with Robot

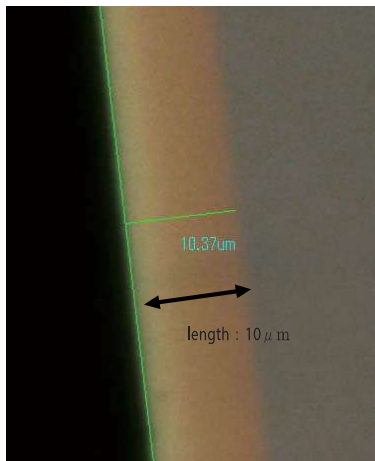
## Specifications

- Substrate size :  $1 \times 6'' \phi$  ,  $1 \times 4'' \phi$   
 $3 \times 3'' \phi$  ,  $7 \times 2'' \phi$
- Substrate heating : Resistance heating type
- Maximum heating temperature :  $600^{\circ}\text{C}$   
(T.C.Value for control)
- Flow control : Liquid mass flow control
- Vaporizer : Heating type Vaporizer(Max. $180^{\circ}\text{C}$ )
- Vacuum exhaust system : Diaphragm pump
- Control system : Programmable Logic controller
- Options : Loder / Unloder

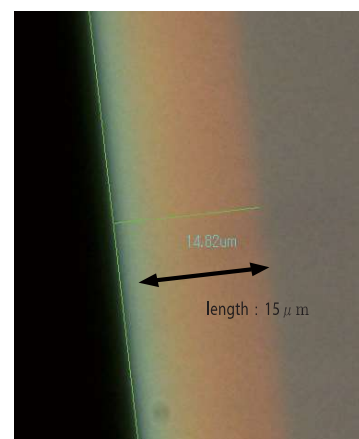


## View

- The image of Sample : (Magnification; 10 X)



Oxidation Temperature :  $450^{\circ}\text{C}$   
Oxidation Time : 10min



Oxidation Temperature :  $450^{\circ}\text{C}$   
Oxidation Time : 15min